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	Application No.	Applicant(s)
Notice of Allowability	10/698,726	DEMOS ET AL.
	Examiner	Art Unit
	Johnnie L Smith II	2881
	Johnnie E Striut II	2001
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308. 1. This communication is responsive to arguments filed 11/01/2004.		
2. X The allowed claim(s) is/are 1-5 and 7-18.		
3. ☑ The drawings filed on <u>30 October 2003</u> are accepted by the Examiner.		
4.		
7. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
Attachment(s)		
1. ☑ Notice of References Cited (PTO-892)		atent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. 🔲 Interview Summary Paper No./Mail Dat	
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date	8), 7. Examiner's Amenda	nent/Comment
4. Examiner's Comment Regarding Requirement for Deposit		ent of Reasons for Allowance
of Biological Material	9.	

DETAILED ACTION

Allowable Subject Matter

- 1. Claims 1-5, 7-18 are allowed.
- The following is an examiner's statement of reasons for allowance: the 2. examiner agrees with applicant arguments filed 11/01/2004. Herein is claimed an electron beam treatment method and apparatus having a chamber further comprising a cathode, an anode, a wafer holder, a gas inlet, sources for negative and positive voltages. With regards to allowability the prior art searched and cited failed to teach or fairly suggest the said method and apparatus wherein values of the cathode voltage, gas pressure In the chamber, and working distance are such that there is no arcing between the cathode and the anode at the working distance that is greater than the means free path of the electrons from the cathode. That claimed limitation in combination with the remaining elements of claims 1 and 8 are considered allowable. Claims 2-5, 7, and 9-11 are considered allowable because of their dependencies upon claims 1 and 8. Claim 12 narrows the working distance to a range from 10 to 20 mm and is considered allowable over the prior art searched and cited. Claims 13-18 are allowable because of their dependencies upon claim 12.

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Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Conclusion

3. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure. US patent 6,417,111 (Nishikawa et al), 5,094,885 (Selbrede), 5,350,480 (Gray), and 5,421,888 (Hasegawa). All of the cited US patents contain art similar to that being claimed by applicant, more specifically, methods and apparatuses having low and high pressure chambers containing electron exposure equipment.

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Johnnie L Smith II whose telephone number is 571-272-2481. The examiner can normally be reached on Monday-Thursday 7-4 P.M. and Alternate Fridays.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, John R Lee can be reached on 571-272-2477. The fax

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phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Johnnie L Smith II

Examiner

Art Unit 2881

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NIKITA WELLS PRIMARY EXAMINED 01/24/05